

List of Nanofabrication Equipment

Lithography & Pattern Transfer Tools

- E-beam Lithography System (Elionix), ELS-7000
- Canon Stepper (FPA3000 EX5 248 nm)
- Mask Aligner (EVG 6200-Infinity)
- Coater/Developer Rite Track
- Optical Laser Writing Tool (Heidelberg), DWL66FS
- Laser Pattern Generator (Heidelberg), DWL2000
- Mask & Bond Aligner (SUSS MicroTec), MA8/BA6
- Mask & Bond Aligner (SUSS MicroTec), MA6
- HMDS/Image Reversal Oven (YES), 310TA
- Nano Imprint Lithography System (Obducat), Eitre
- Roll-to-Roll UV Nanoimprint System (SOLVES)
- Roll-to-Plate Nanoimprint System
- Thermal Roll-to-Roll Nanoimprint System (SOLVES)

Deposition Tools

- Plasma Enhanced Chemical Vapor Deposition System (Unaxis), Nextral ND200
- Low Pressure Chemical Vapor Deposition System (Centrotherm), E1200 HT 260-4
- RF/DC Sputtering System 1 (Denton), Discovery 18
- RF/DC Sputtering System 2 (Denton), Discovery 18
- Unbalanced Magnetron Sputtering System (Nanofilm)
- E-Beam Evaporator 1 (Edwards), Auto 306
- E-Beam Evaporator 2 (Edwards), Auto 306
- E-Beam Evaporator 1 (Denton), Explorer
- E-Beam Evaporator 2 (Denton), Explorer
- PECVD System (Oxford), Plasmalab System 100 ICP380
- PVD Platform (Angstrom Engineering), EvoVac
- ALD System (Picosun), R-200 System
- Dual-Beam Ion Assisted Deposition (Oxford), Optofab 3000
- Ion Beam Etch and Deposition System, (Oxford), Ionfab 300Plus
- PVD Production Platform (Singular), Timaris
- Sputtering System (Singular), Rotaris
- PVD System (AMAT), Endura 5500
- CVD System (AMAT), Producer
- SAM Coater (Sorona), AVC-150M

Etching Tools

- Inductive Coupled Plasma Etching System (Unaxis), Shuttle Lock Reactor SLR-7701-8R
- DRIE/ICP Etcher (Oxford), Plasmalab ICP 180
- RIE II Etcher (Oxford), Plasmalab 80plus
- RIE I Etcher (Trion), SIRUS

- Reactive Ion Etcher (Trion), Sirius T2
- UV & Ozone Dry Stripper (Samco), UV-I
- XeF2 Silicon Dry Etching System (Xactix), Xetch eI
- ICP-RIE Fluorine (Oxford), I00 Cobra
- ICP-RIE Chlorine (Oxford), PlasmaPro System I00 Cobra
- Advanced Dielectric Etcher (SPTS), LPX APS
- Etch System (LAM), EXELAN 2300
- Ion Beam Etch and Deposition System, (Oxford), Ionfab 300Plus
- Resist Ashing System (Axcelis), Fusion Gemini

Thermal Processing Tools

- Rapid Thermal Processing System (Jipelec), JetFirst I50
- Conventional Furnace (Thermcraft)
- Furnace First Nano tube 6000

Backend Process Tools

- Lapping/ Polishing Machine (Kemet), Kemet 48
- Semi-Automatic Wafer CMP System (Okamoto Model SPP600S)
- Dicing system (Disco), DAD32I
- Laser Processing System (ESI), 5200
- Laser Cutter (IDI)

Electroplating Tools

- Nickel electroplating system I
- Nickel electroplating system II